A Complementary Design Theory for Doubling

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Based on

Chen, H. and Cheng, C.S. (2006) Annals of Statistics,

ongoing work with Hongquan Xu,

and some results from the literature of finite projective geometry (Davydov & Tombak, 1990; Bruen, Haddad and Wehlau, 1998; Bruen & Wehlau, 1999) Objective: construction of two-level minimum aberration (*regular*) fractional factorial designs

 $X: N \times n$ matrix with entries 1 and -1N : run size n: # of factors

 $N = 2^{n-p}$

 2^{n-p} fractional factorial design

 2^{5-2} :



Defining relation:

I = ABD = ABCE = CDE

Resolution: length of the shortest word in the defining relation

Resolution III: no aliasing among main effects

Resolution IV: no aliasing of main effects with other main effects and two-factor interactions

Minimum aberration (Fries & Hunter, 1980): Sequentially minimize A_3, A_4, \cdots , where A_k = number of words of length k in the defining relation.

Only resolution III+ (resolution III or higher) designs are considered: $A_1 = A_2 = 0$.

• Minimize the aliasing among lower order effects

 (A_3, A_4, \cdots) : Word length pattern

Doubling

$$D(\boldsymbol{X}) = \begin{bmatrix} \boldsymbol{X} & \boldsymbol{X} \\ \boldsymbol{X} & -\boldsymbol{X} \end{bmatrix} = \begin{bmatrix} 1 & 1 \\ 1 & -1 \end{bmatrix} \otimes \boldsymbol{X}$$

Two facts:

(i) ∃ a two-level design of resolution III+
⇒ n ≤ N - 1.
(ii) ∃ a two-level design of resolution IV+
⇒ n ≤ N/2.

A two-level design of resolution III is called *saturated* if n = N - 1.

 $\leftarrow \text{Max. resolution} = 3 \rightarrow$

n: N-1 N/2

 \rightarrow Max resolution ≥ 4

Saturated regular designs of resolution III are unique (up to isomorphism).

For $N = 2^k$, a saturated design of resolution III can be obtained by deleting the first column of

$$\underbrace{\begin{bmatrix} 1 & 1 \\ 1 & -1 \end{bmatrix} \otimes \begin{bmatrix} 1 & 1 \\ 1 & -1 \end{bmatrix} \otimes \cdots \otimes \begin{bmatrix} 1 & 1 \\ 1 & -1 \end{bmatrix}}_{k}.$$
repeated double of
$$\begin{bmatrix} 1 & 1 \\ 1 & -1 \end{bmatrix}.$$

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Resolution IV designs with n = N/2 are also unique (up to isomorphism), and can be obtained by *folding over* saturated designs of resolution III.

If X is a 2^{n-p} design of resolution III, then

$$\begin{bmatrix} \mathbf{1} & \mathbf{X} \\ -\mathbf{1} & -\mathbf{X} \end{bmatrix}$$
 is a $2^{(n+1)-p}$ design of resolution IV.

Resolution IV designs with n = N/2 can also be obtained by *repeatedly doubling the* 2^1 *design*. Saturated designs of resolution III are *maximal* (the resolution is reduced to two whenever a factor is added), and they are the *only* maximal designs of resolution III.

Every fractional factorial design of resolution III+ can be obtained by choosing columns from a saturated design of resolution III (or we say that it's a *projection* of the saturated design of resolution III.) Resolution IV designs with n = N/2 are *maximal* designs of resolution IV (the resolution is reduced to three whenever a factor is added). Unlike saturated designs of resolution III, they are *not* the only maximal designs of resolution IV.

Resolution IV designs with n = N/2 are even designs in the sense that $A_i = 0$ for all odd *i* (a consequence of foldover). They are the only even designs that are maximal. We shall call them the maximal even designs. There is *exactly one* maximal design of resolution IV with n = 5N/16, and there is no maximal design of resolution IV with 5N/16 < n < N/2.

The maximal design of resolution IV with n = 5N/16 can be constructed by repeatedly doubling the 2_V^{5-1} design defined by I = ABCDE.

There is *exactly one* maximal design of resolution IV with n = 9N/32, and there is no maximal design of resolution IV with 9N/32 < n < 5N/16.

The maximal design of resolution IV with $n = \frac{9N}{32}$ can be constructed by repeatedly doubling a 2^{9-4} design.

There are *five* maximal designs of resolution IV with n = 17N/64, and there is no maximal design of resolution IV with 17N/64 < n < 9N/32.

Each maximal design of resolution IV with $n = \frac{17N}{64}$ can be constructed by repeatedly doubling a 2^{17-11} design.

Block and Mee (2003)'s computer search found *five* 2^{17-11} maximal designs of resolution IV.

If $N = 2^k$, $k \ge 4$, then for $\frac{N}{4} + 1 \le n \le \frac{N}{2}$, a maximal regular design of resolution IV or higher exists *if and only if* n is an integer of the forms $\frac{N}{2}, \frac{5}{16}N, \frac{9}{32}N, \frac{17}{64}N, \frac{33}{128}N, \cdots$

Such a design with $n = \frac{2^{i}+1}{2^{i+2}}N$ can be constructed by *repeatedly doubling* a maximal 2^{i+2} -run design with $2^{i} + 1$ factors.







 2^{1-0}

The maximal 2^{5-1} , 2^{9-4} and 2^{17-11} designs of resolution IV are *partial* foldovers of the 2^{4-1} , 2^{8-4} and 2^{16-11} maximal even designs.

Let X be a maximal even design with N/2 runs and N/4 factors. Partition X so that $X = [B \ C]$, and create the N-run design

$$S = egin{bmatrix} 1 & B & C \ -1 & -B & C \end{bmatrix}$$

with N/4 + 1 factors. Then S has resolution IV. It is maximal if B contains an *odd* number of columns. When B contains an *even* number of columns, Smay or may not be maximal. Complementary design theory

Every regular design D of resolution III+ is a *projection* of the saturated regular design of resolution III.

The factors that are not chosen form another design \overline{D} , called the *complementary* design of D.

Chen and Hedayat (1996 *AS*) and Tang and Wu (1996 *AS*) found a relationship between the wordlength patterns of D and \overline{D} . The construction of D can be done via selecting \overline{D} . This is useful when d is *nearly saturated*.

 $A_k(\boldsymbol{D})$ can be determined by $\{A_i(\boldsymbol{\overline{D}})\}_{i \leq k}$. MA \Leftrightarrow sequentially minimizing $(-1)^k A_k(\boldsymbol{\overline{D}})$.

Not useful when n < N/2.

For 5N/16 < n < N/2, a minimum aberration design is of resolution IV, and must be a projection of the maximal even design.

A complementary design theory was developed by Butler (2003).

Hegang Chen's talk tomorrow.

For an $N_0 \times n_0$ design X_0 , let X be obtained by doubling X_0 t times.

Suppose D and \overline{D} are a pair of complementary subdesigns of X.

There are identities relating the word length pattern of D to that of \overline{D} , covering the results of Chen and Hedayat (1996), Tang & Wu (1996) and Butler (2003) as special cases.

$$A_k(\boldsymbol{D}) = (-1)^k A_k(\overline{\boldsymbol{D}}) + c_{k-1} A_{k-1}(\overline{\boldsymbol{D}}) + \dots + c_1 A_1(\overline{\boldsymbol{D}}) + c_0 + d_k \Delta_k(\boldsymbol{D}, \overline{\boldsymbol{D}}) + \dots + d_1 \Delta_1(\boldsymbol{D}, \overline{\boldsymbol{D}})$$

where

$$\Delta_k(\boldsymbol{D}, \, \overline{\boldsymbol{D}}) = \sum_{i=1}^{N_0} [W_i(\boldsymbol{D})^k - (n/2 - W_i(\overline{\boldsymbol{D}}))^k], n = n_0 2^t$$

 $W_i(\boldsymbol{D})$ is the Hamming weight of the *i*th row of \boldsymbol{D}

Technical tool: Pless power moment identities

Each column of X_0 generates 2^t columns of X. Suppose D contains f_i columns that are generated by the *i*th column of X_0 . Then $\Delta_k(D, \overline{D})$ depends on X_0 and f_1, \dots, f_{n_0} .

When applied to saturated designs of resolution III and maximal even designs, $\Delta_k(\boldsymbol{D}, \boldsymbol{\overline{D}})$ does not depend on f_1, \dots, f_{n_0} . **Theorem** (Chen & Hedayat, 1996; Tang and Wu, 1996). Let X be the saturated design of resolution III. If D consists of u columns of X, then D has minimum aberration among all possible u-factor designs if $-A_3(\overline{D})$, $A_4(\overline{D})$, $-A_5(\overline{D})$, $A_6(\overline{D})$, $-A_7(\overline{D})$, \cdots are sequentially minimized.

Theorem (Butler, 2003). Let X be a maximal even design. If D consists of u columns of X and \overline{D} is the complement of D in X, then D has minimum aberration among all possible u-factor projections of X (and hence has minimum aberration among all u-factor designs) if $A_4(\overline{D})$, $A_6(\overline{D})$, $A_8(\overline{D})$, \cdots are sequentially minimized.

All projections of the maximal even design are even designs.

Theorem. Let X be the maximal design obtained by doubling the 2_V^{5-1} design t times. If D consists of certain u columns of X and \overline{D} is the complement of \overline{D} in X, then for $u \leq 15 \cdot 2^{t-3}$, D has minimum aberration among all possible u-factor projections of X if

(i) $A_4(\overline{D}), -A_5(\overline{D}), A_6(\overline{D}), -A_7(\overline{D}), \cdots$ are sequentially minimized.

(ii) $|f_i - f_j| \le 1$ for all $1 \le i < j \le 5$.







 2^{1-0}

For $N/4 + 1 \le n \le 5N/16$, all projections of the maximal even design are worse than some projections of the maximal design with n = 5N/16.

For $N/4 + 1 \le n \le 5N/16$, all projections of the maximal design with 9N/32 are also worse than some projections of the maximal design with n = 5N/16.

Theorem. For $17N/64 \le n \le 5N/16$, minimum aberration designs are projections of the maximal design obtained by repeatedly doubling the 2_V^{5-1} design.

Conjecture. The above theorem holds for $N/4 + 1 \le n \le 5N/16$.

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